IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office on May 28, 2009 at or before 11:59 p.m. Pacific Time under the Rules of 37 CAR § 1.8.

C. Healion

Apple No. : 10/587,194 Confirmation No. 8444

Applicant : Jean-Louis Stehle Filed : July 24, 2006

Title : PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY

IN THE EXTREME UV OR SOFT X-RAY RANGE

TC/A.U. : 1795

Examiner : Jonathan G. Jelsma

Docket No. : 58059/N75 Customer No. : 23363

AMENDMENT

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Post Office Box 7068 Pasadena, CA 91109-7068 May 28, 2009

Commissioner:

In response to the Office action of November 28, 2009, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.